

Method for Preparing Photomask Blank, Photomask Blank,
Method for Preparing Photomask, Photomask, and Metallic Chromium Target

ABSTRACT

5

A method for preparing a photomask blank comprising a transparent substrate and a chromium-containing film contiguous thereto involves the step of depositing the chromium-containing film by sputtering a metallic chromium target having an Ag content of up to 1 ppm. When a photomask prepared from the photomask blank is repeatedly used
10 in patternwise exposure to ArF excimer laser radiation, the number of defects formed on the photomask is minimized.

[FIG. 1]